

Fundamental Study of Metal/Oxide/Metal Memristor Physics and Device Optimization

Sandia National Laboratories

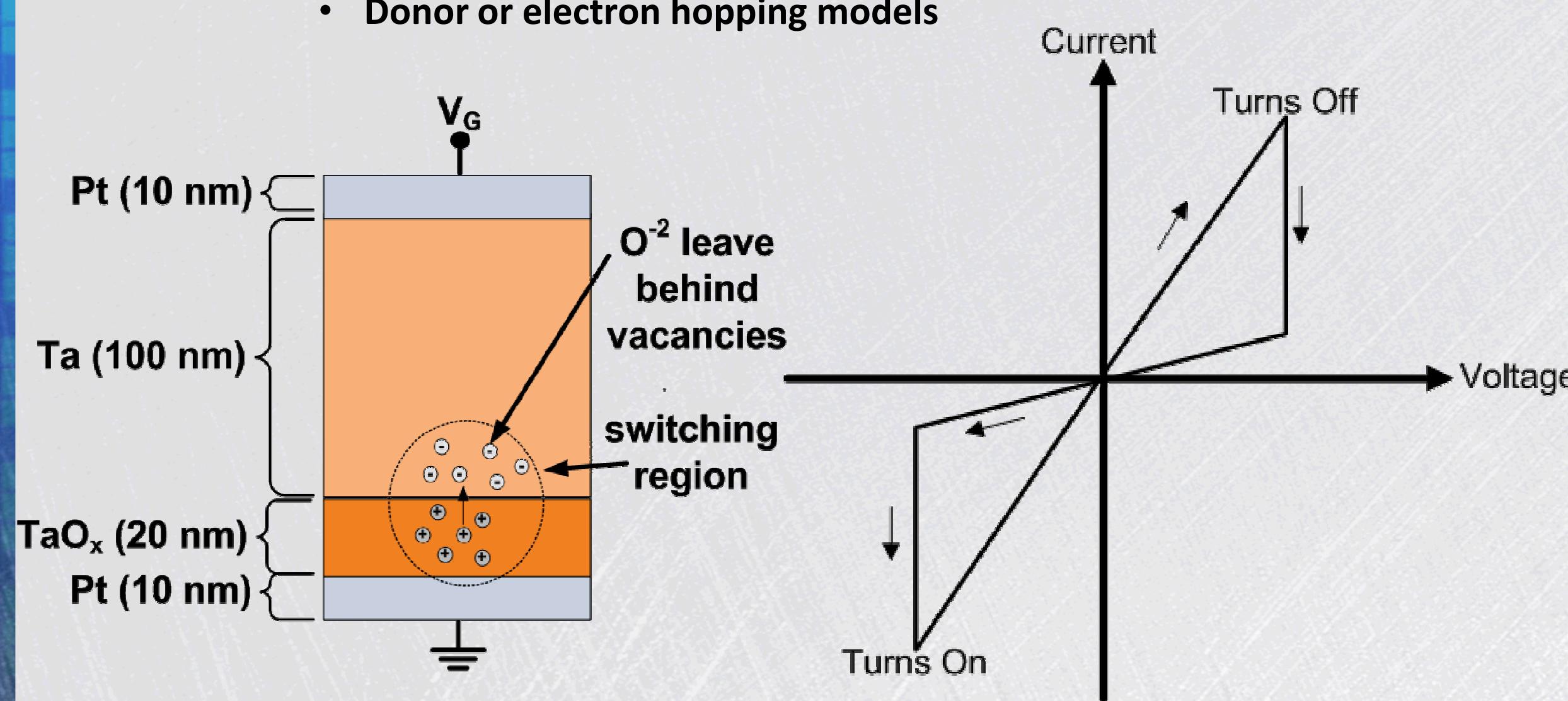
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Early Career R&D Program

Problem

- The Memristor or Resistive/Redox RAM (RRAM) is one of the most promising replacements for Flash, DRAM, and even SRAM memories
- Poor physical understanding of switching action has limited the use of this technology
- Problem: Insufficient understanding of switching mechanism
- Current working theories:
 - Conductivity modulated by O²⁻ anion migration
 - Filament formation
 - Donor or electron hopping models



Approach

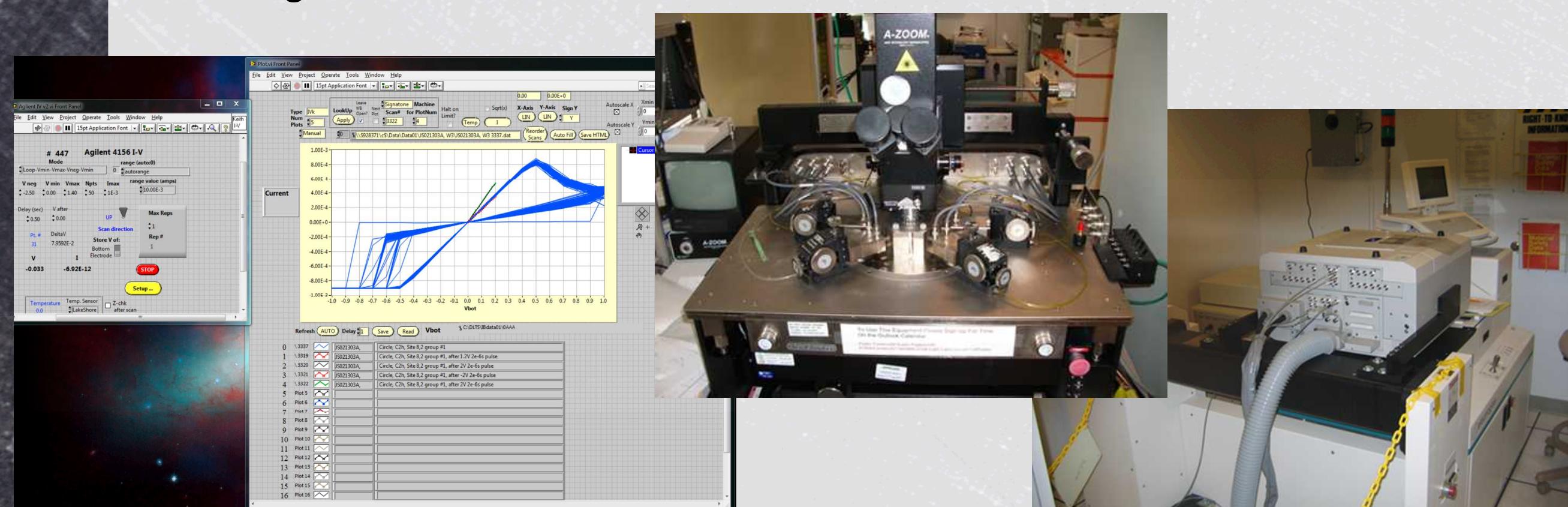
- Project Plan: Make memristors and use electrical characterization and modeling to understand switching
- Focus on transition metal oxide (TMO) memristors
- Initial major risk – fabricating inexpensive but stable, working memristors
- Fabrication Approach: Two methods of device fabrication

1. Sol-gel ZnO deposition on TMO substrate
2. Simple MESAFab flow to create metal/oxide/metal capacitors

MESAFab Flow

1. Dep blanket TiN/Al
2. Deposit metal oxide (XXX)
3. Dep top ~7k W
4. Pattern dots
5. Wet etch W dots
6. Dep backside Al

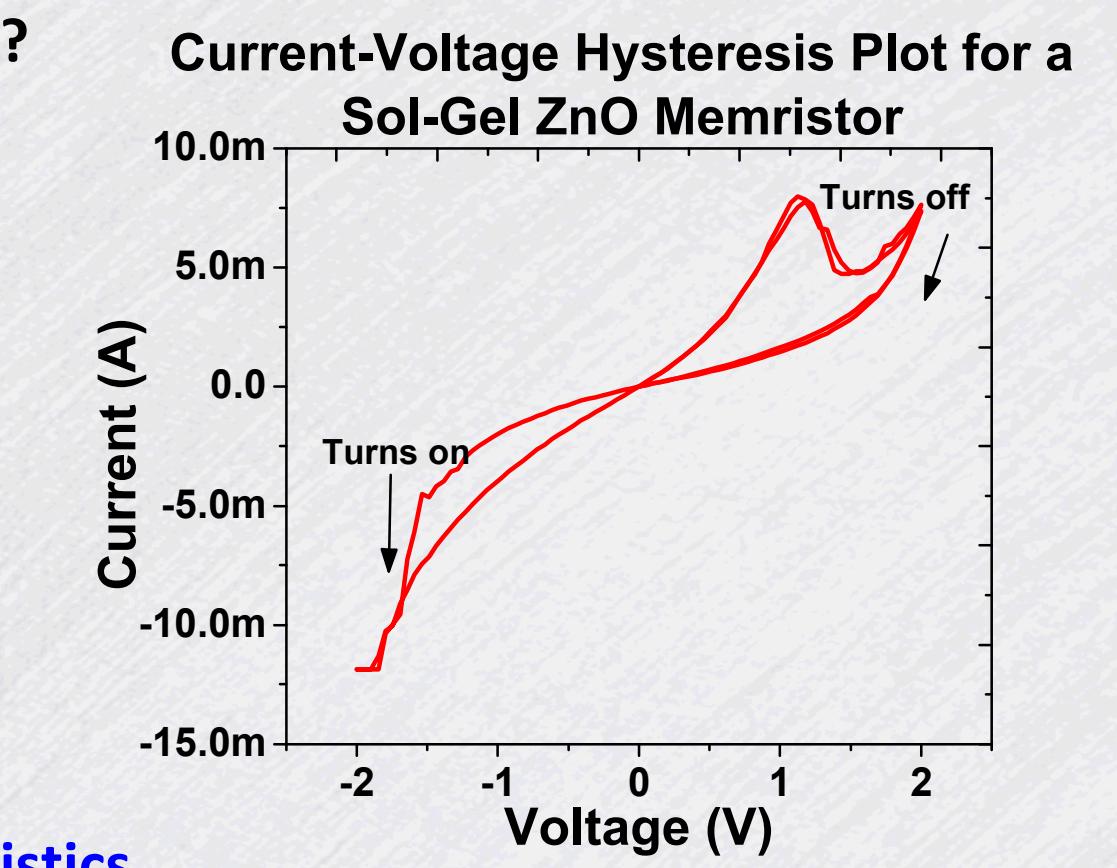
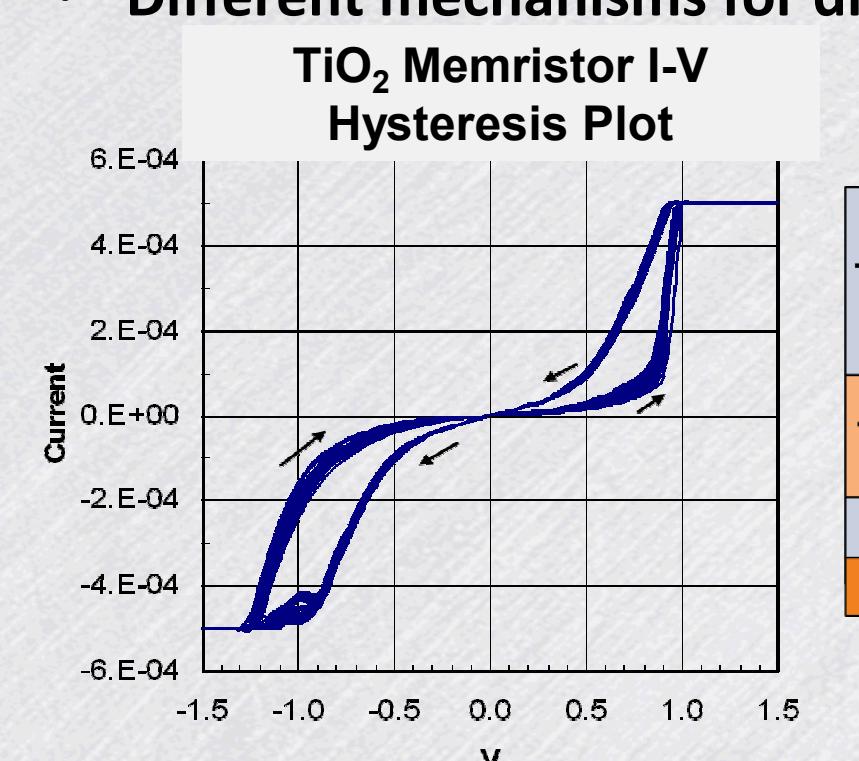
- Electrical Characterization Approach: Match a Common Insulator Conduction Mechanism
- Examples: Ohmic, Ionic, Tunneling, Frenkel-Poole, Schottky Emission
- 2 Main Factors:
 1. Current – Voltage Relationship
 2. Current – Temperature Relationship
- Make use of 1748 rad-hard CMOS/advance device parametric test lab and Robert Fleming's extensive LabVIEW test suite



Results

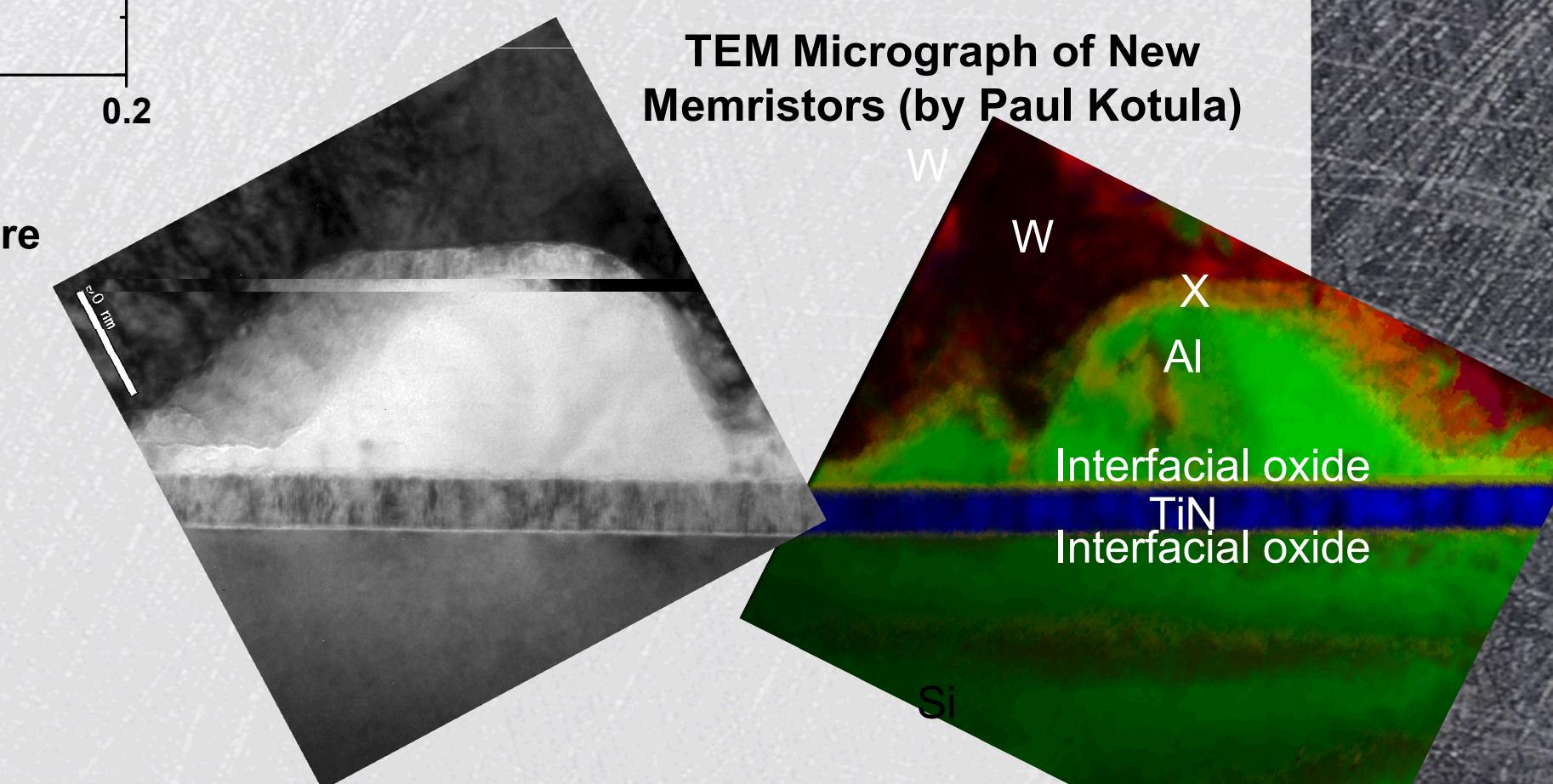
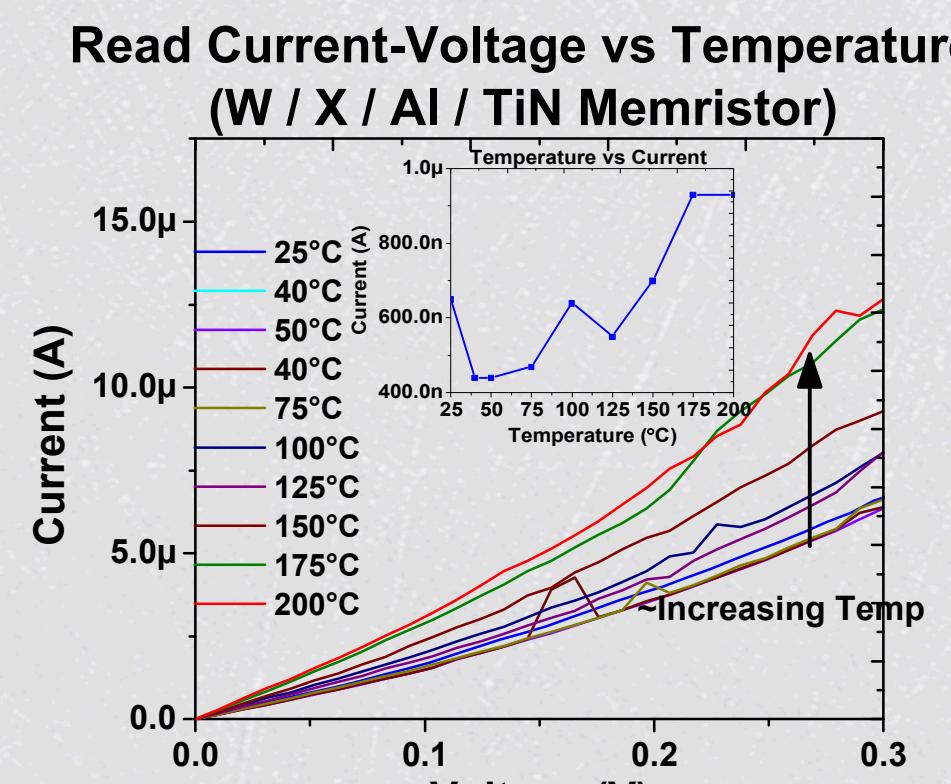
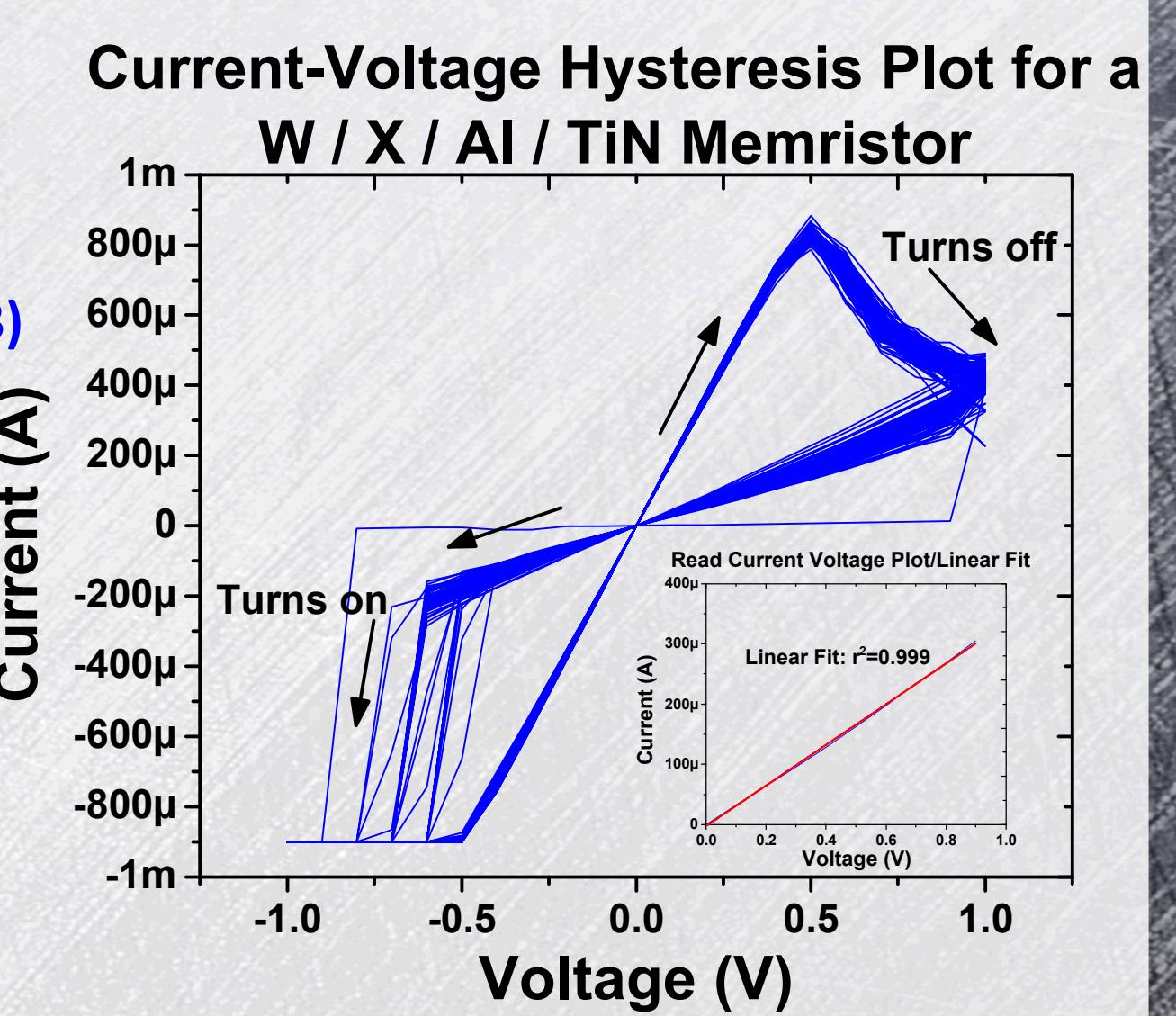
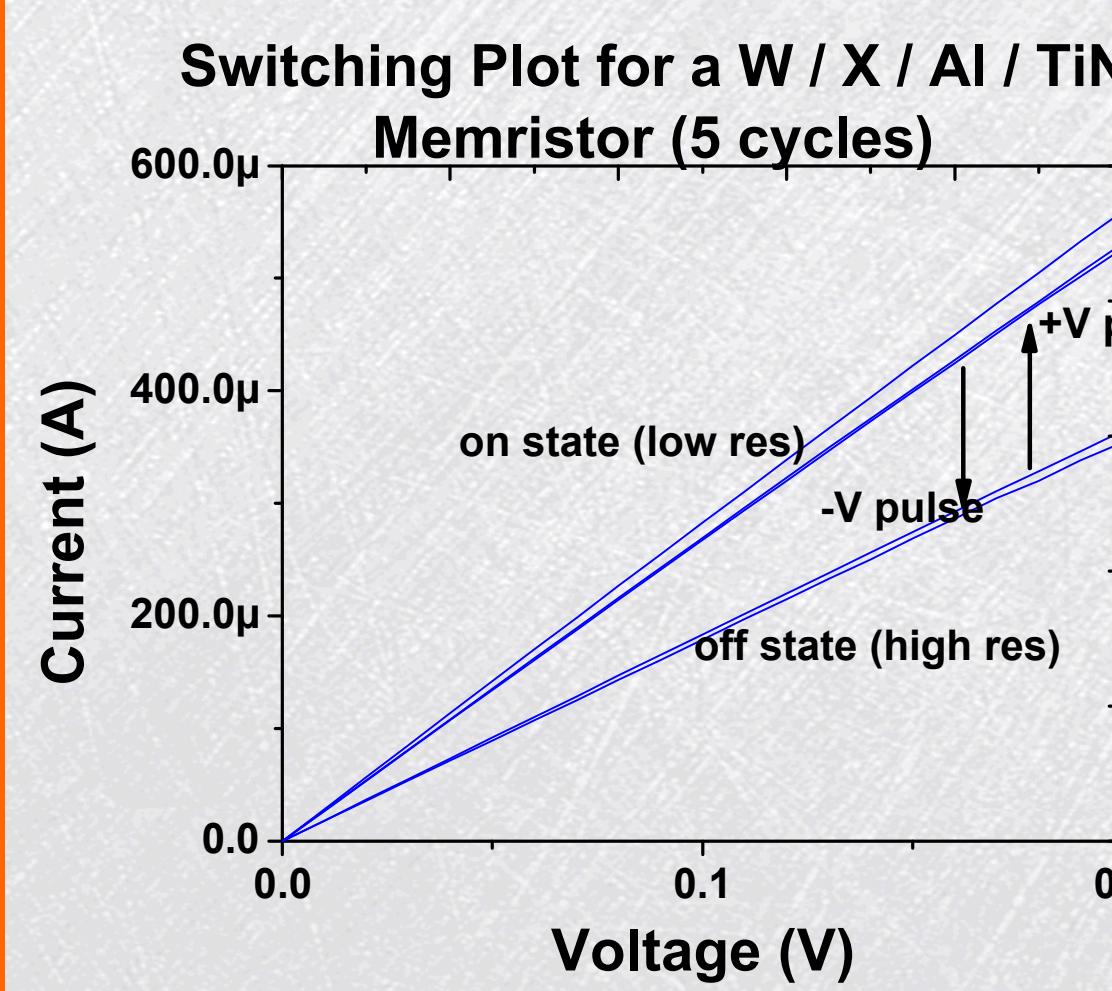
Each fabrication approach resulted in working devices:

- Chemistry lab: Sol-gel ZnO demonstrated (TiO₂ possible also)
- Fab: TiO₂, WO, and a new, promising material demonstrated, TaO_x samples from HP and in progress in uFab
- Variety of electrical characteristics for on and off I-V curves
- Different mechanisms for different materials?



Invented new memristor with promising characteristics

- 150 cycles, on/off pulsing demonstrated
- Highly linear I-V – Ohmic conduction?
- High on/off ratio possible
- New material questions current models
- TA submitted for new material (SD 12053)



Need a combination of physical and electrical characterization to understand switching!

- New NTM LDRD has been proposed and accepted to study physics of memristor switching

Significance

- Sandia has gained the ability to fabricate memristors from a number of materials
- A new memristor has been invented (SD 12053)
- Electrical modeling reveals different likely mechanisms for different materials
- Need a combination of physical and electrical characterization to understand switching!
- Memristors represent a new technology with major potential in numerous applications
 - Flash, DRAM, SRAM replacement, rad-hard memory, neuromorphic systems, and national security applications
- Two new follow-on LDRDs have been Funded for FY12 to continue and expand this work:
 - NTM LDRD to study physics of switching in TaO_x memristors
 - Cyber security LDRD
 - One of the disruptive memory technologies for the Exascale Grand Challenge
- Other activities initiated by this work:
 - CRADA with Industrial Research Lab
 - Two external funded projects and major proposals
 - Collaborations initiated – Arizona State University, Boston University, and Industrial Partners